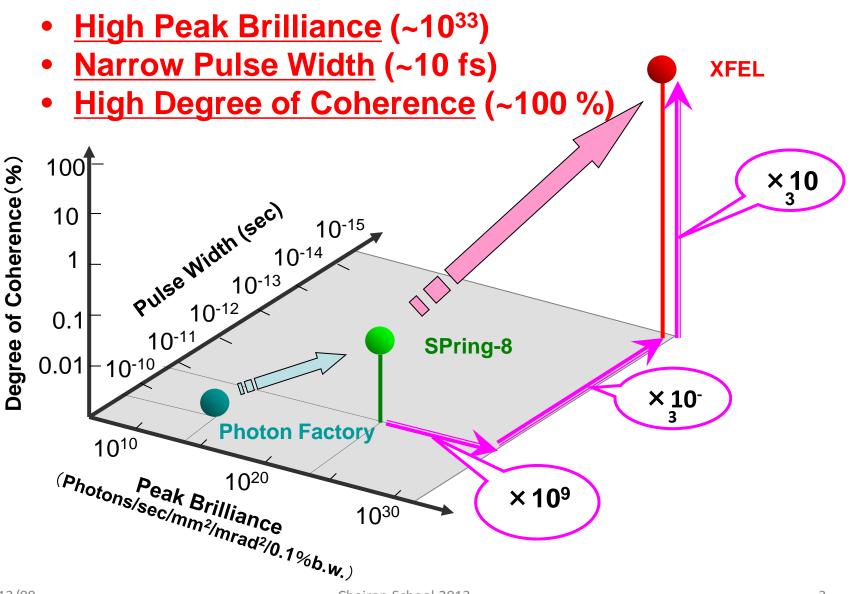
X-ray Free Electron Laser Part-1 Accelerator Part

XFEL Research & Development Division RIKEN SPring-8 Center Hitoshi Tanaka

Outline

- Introduction –What we can observe using XFEL
- 2. Overview of SASE XFEL
- 3. Approach to compact XFEL
- 4. Performance of XFEL

Remarkable Features of XFEL

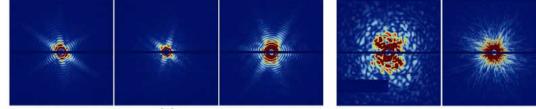


1. What XFEL enables us to observe

Coherence

Structure analysis on non-crystalline material (e.g., amorphous,

single particle)



Ultrafast

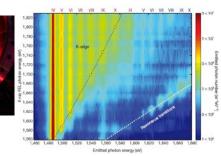
Structure/Electric properties probed with fs temporal resolution

(e.g. ultrafast phase transition)



Physics in highly-excited/extreme state under ultra-intense

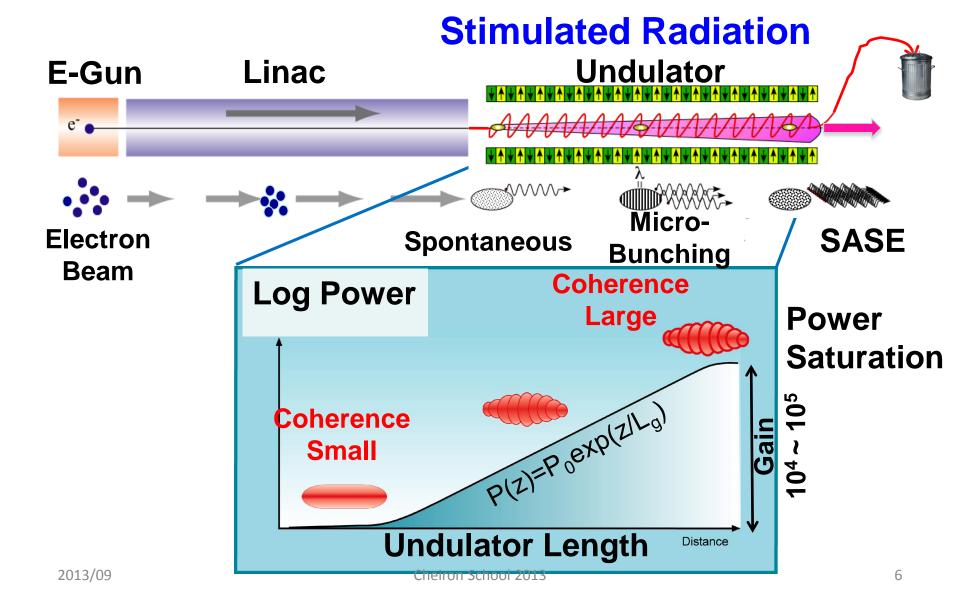
optical field (e.g. high density state)



VO, Insulator

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SASE XFEL Scheme

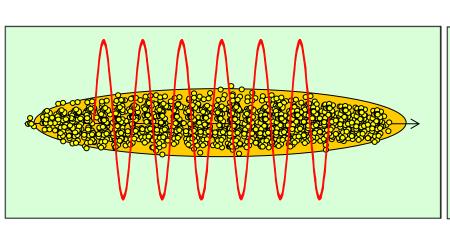


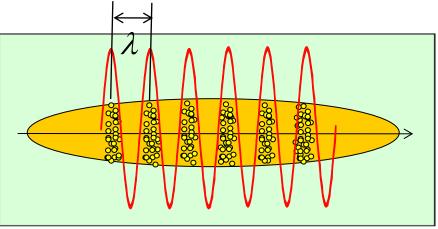
Free electrons as a laser medium

Resonance condition

$$\lambda = \lambda_u - \overline{v}_z T \approx \frac{\lambda_u}{2\gamma^2} \left(1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right), K = \frac{eB\lambda_u}{2\pi m_0 c\gamma}$$

Electron beam is trapped in an electro-magnetic potential and this potential generates energy modulation around the stable fixed point. Then the energy modulation is converted to density modulation through the energy dispersion of the undulator.





Free electrons as a laser medium

Instead of stimulated emission, the density modulated electrons with an interval of a resonance wavelength λ , enables laser amplification.

- Independent on energy level in atoms and molecules -

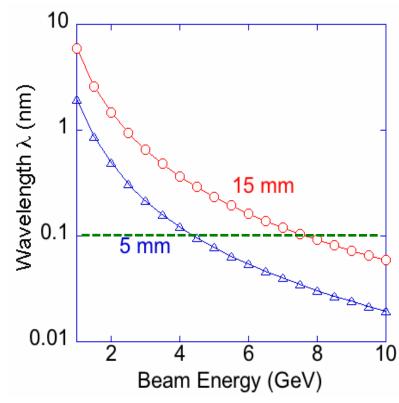
$$\lambda = \frac{\lambda_u}{2\gamma^2} \left(1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right), K \cong 1 \sim 2$$

Let's estimate λ assuming

$$\lambda_u$$
=15mm, K=2,
 γ =3915@2GeV



$$\lambda = 1.5 \text{ nm}$$



Single pass laser system removing an optical cavity requires highly brilliant electron beam + long undulator with a large number of periods

<Brilliant electron beam>

High electron density achieving a high gain and low angular divergence keeping density modulation of Å order.

<Long undulator>

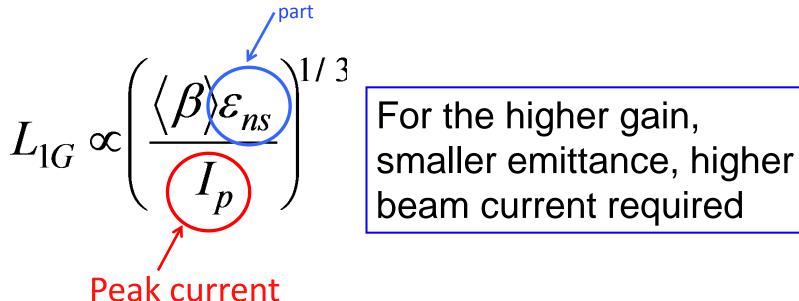
A larger number of periods realizes a sufficiently high gain by a single pass, which corresponds to that obtained by the optical cavity system.

Laser Amplification Gain

$$L_{1G} = \frac{\lambda_u}{4\sqrt{3}\pi\rho}, \qquad \rho = \left(\frac{K}{4\gamma}\sqrt{F_1(K)}\frac{\Omega_\rho}{\omega_u}\right)^{\frac{2}{3}}, \qquad \omega_u = \frac{2\pi c}{\lambda_u}, \qquad n_e = \frac{N_e}{\sigma_\ell\sigma_\chi\sigma_\chi},$$

$$F_1(K) = \left(J_0(\xi) - J_1(\xi)\right)^2, \quad \xi = \frac{K^2}{2(1+K^2)}, \qquad \Omega_\rho = \left(\frac{4\pi c^2 r_e n_e}{\gamma}\right)^{\frac{1}{2}},$$

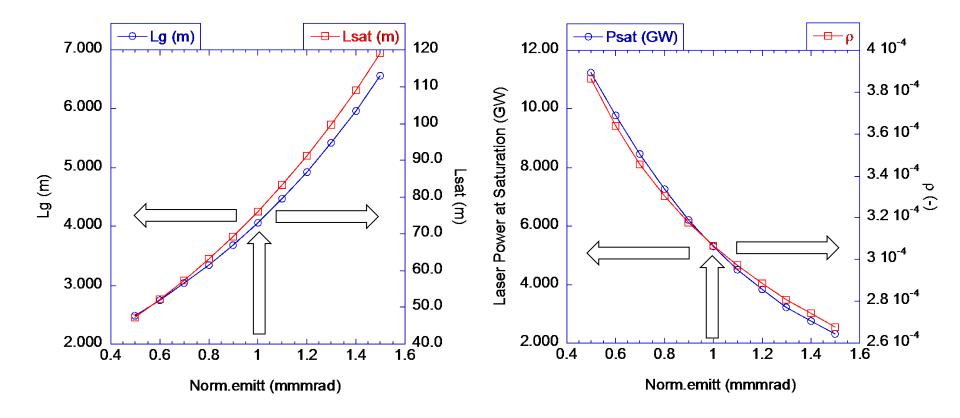
Normalized emittance at a lasing



beam current required

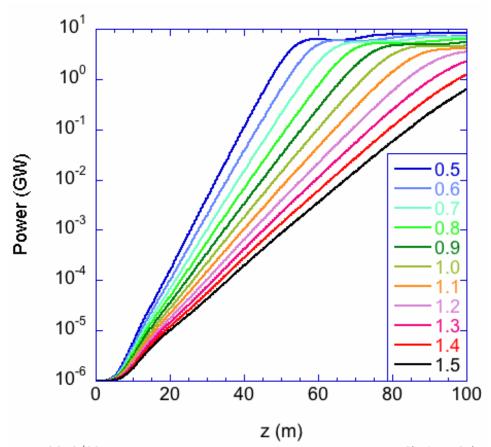
Laser Amplification Gain

 $\lambda_{\text{SASE}} = 1 \text{ Å}$, K=1.85, $\lambda_{\text{u}} = 18 \text{ mm}$, E=8 GeV, $I_{\text{p}} = 3 \text{ kA}$, $\Delta E/E = 4 \times 10^{-5}$, $\beta_{\text{ave}} \sim 30 \text{ m}$,



Laser Amplification Gain

 $\lambda_{\text{SASE}} = 1 \text{ Å}$, K=1.85, $\lambda_{\text{u}} = 18 \text{ mm}$, E=8 GeV, $I_{\text{p}} = 3 \text{ kA}$, $\Delta E/E = 4 \times 10^{-5}$, $\beta_{\text{ave}} \sim 30 \text{ m}$,



For the higher laser power, accurate overlap between laser field and electron beam along a certain distance, 15 to 25 m

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Shortening laser wavelength by high energy electron beam + short-period undulators

<High energy electron beam>

Undulator radiation wavelength depending on the inverse of gamma square

<Short period undulators>

Undulator radiation (laser) wavelength being proportional to the undulator period

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Future Perspective

Although variety of XFEL applications are expected, one facility can provide only a few BLs.

To widely utilize XFEL, it is essential to make the facility scale compact as much as we can. World's trend goes to this direction as XFEL usefulness becomes gradually clear.

Leading three XFEL



Development Target

SPring-8 Compact SASE Source (SCSS) Concept



Compact, cheaper, but high-performance

versus



Wavelength of undulator radiation r

$$\lambda = \frac{\lambda u}{2n\gamma^2} \left(1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right)$$

To generate X-ray with lower beam energy requires a shorter undulator period and smaller K-value

Design Concept of SPring-8 Compact SASE

Source (SCSS)

Lower Beam Energyr



Size Reduction

Efficient Acceleration



Further Size Reduction

Smaller K

Smaller Normalized Beam Emittance



Short period in-vacuum undulator

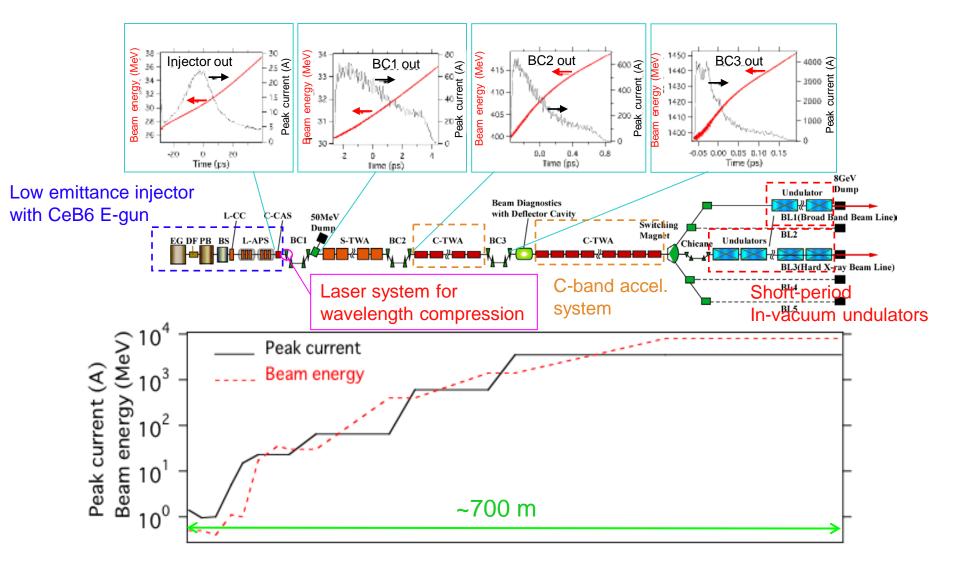


C-band high gradient acceleration system



Themionic gun based low emittance injector

Compact design for 8-GeV SASE XFEL



Design Performance of XFEL

Comparison with SPring-8 performance

Parameter	XFEL	SPring-8
 Wavelength(fundamental) 	>0.06 Å	>0.05 Å
 Pulse Duration 	<100 fs	~40 ps
Repitition MHz	<u><</u> 60) Hz ~40
 Spatial Coherence 	100%	~0.1%
 Peak Power 	20~30 GV	V 100~200 W
 Peak Brilliance 	~10 ³⁴	~10 ²⁴
 Averaged Brilliance 	~10 ²²	~10 ²¹

Def of Brilliance: phs/sec/mrad²/mm²

XFEL/SPring-8 Beamline Technical Design Report Ver. 1.0, June 17 (2008)

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